

EUROPEAN PATENT OFFICE

Patent Abstracts of Japan

PUBLICATION NUMBER : 01265513
PUBLICATION DATE : 23-10-89

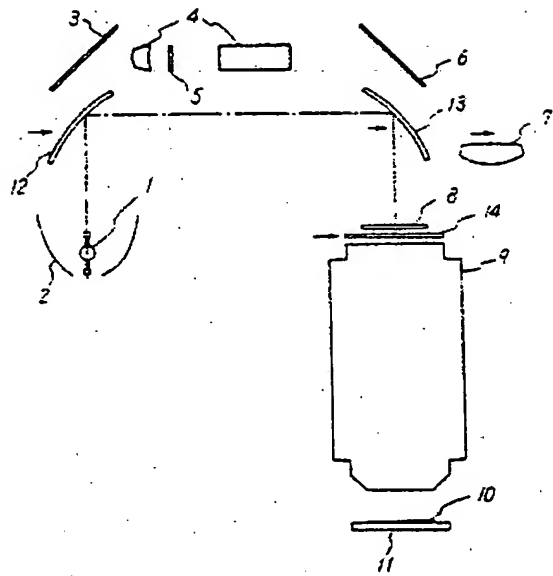
APPLICATION DATE : 15-04-88
APPLICATION NUMBER : 63093079

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INT.CL. : H01L 21/30 G02B 5/10 G02B 26/08
G03F 7/20 G03G 15/02 H01L 21/304

TITLE : REDUCTION PROJECTION ALIGNER



ABSTRACT : PURPOSE: To suppress the occurrence of defective articles by a method wherein ultraviolet rays of shortwaves are projected on a reticle, and the organic dust adhering to the reticle is washed away by conducting a dry cleaning.

CONSTITUTION: A capacitor lens 7, spherical mirrors 12 and 13, and a light-shielding plate 14 are shifted. The light emitting from an exposing light source 1 is reflected by an oval mirror 2, the light is reflected by the spherical mirrors 12 and 13, on which a coating is provided so as to reflect the shortwave ultraviolet rays, which are especially effective for a dry cleaning, and the ultraviolet rays are uniformly applied to the whole surface of the reticle 8. The ultraviolet rays have the effect of cutting the organic chemical bonding, the rays are absorbed into the oxygen in the air, and ozone is generated. The ozone has a strong oxidizing action, it is combined with the carbon, hydrogen and the like in an organic compound, it is decomposed and removed by a volatile substance. As a result, the organic dust on the reticle is washed away, and the occurrence of defective articles can be suppressed.

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